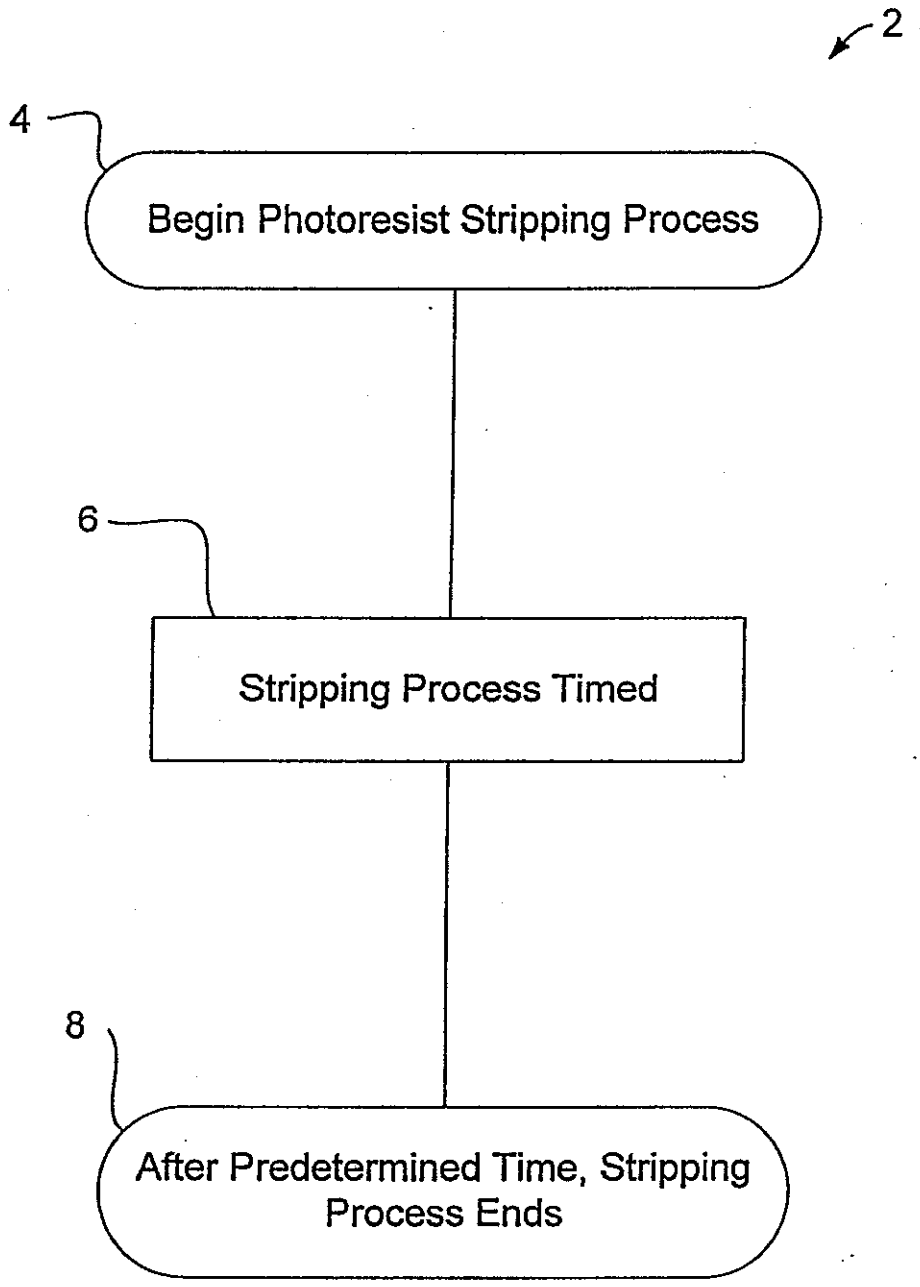


Fig. 1 (Prior Art)

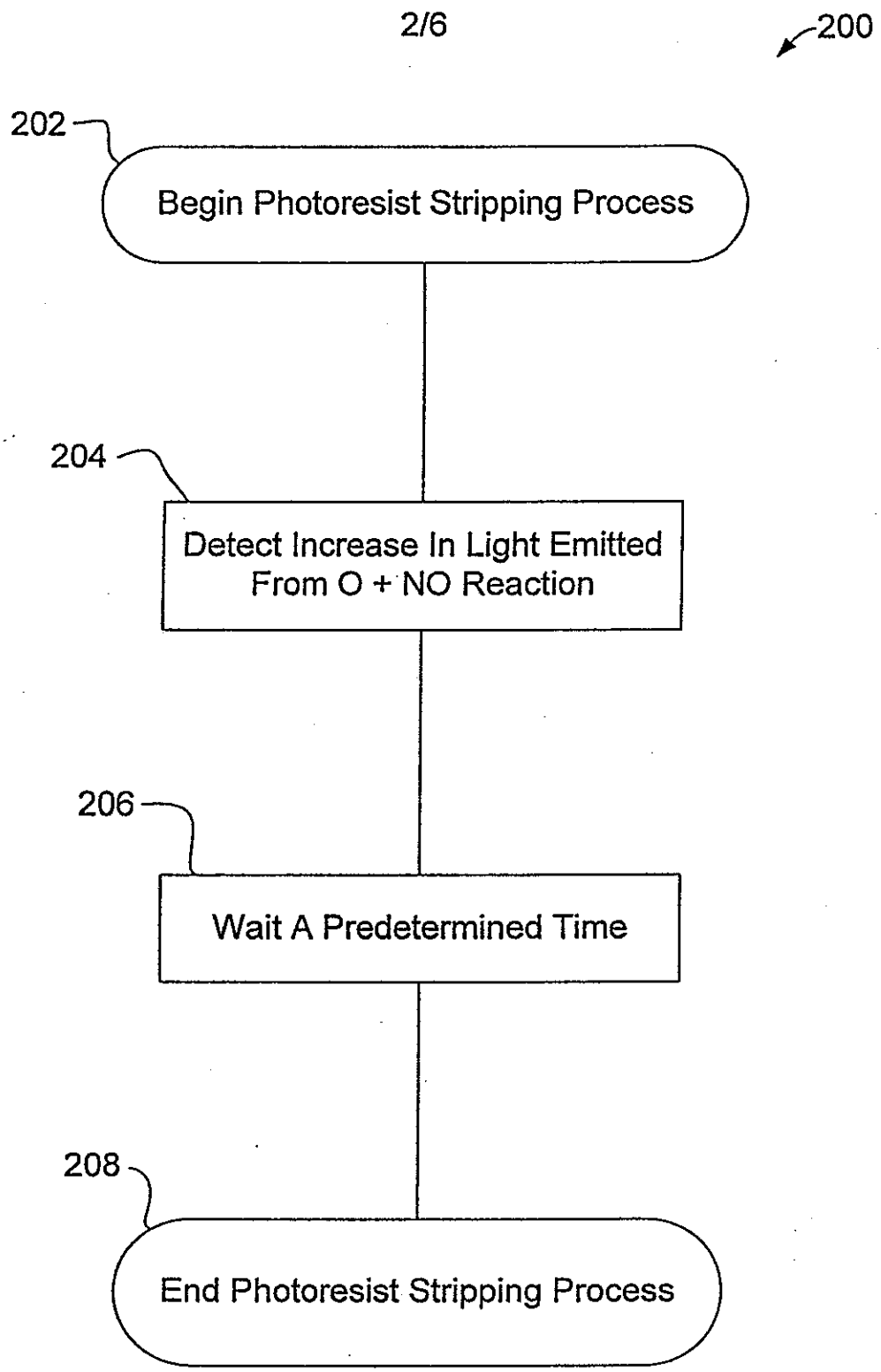

200
202
Begin Photoresist Stripping Process
204
Detect Increase In Light Emitted From O + NO Reaction
206
Wait A Predetermined Time
208
End Photoresist Stripping Process

Fig. 2

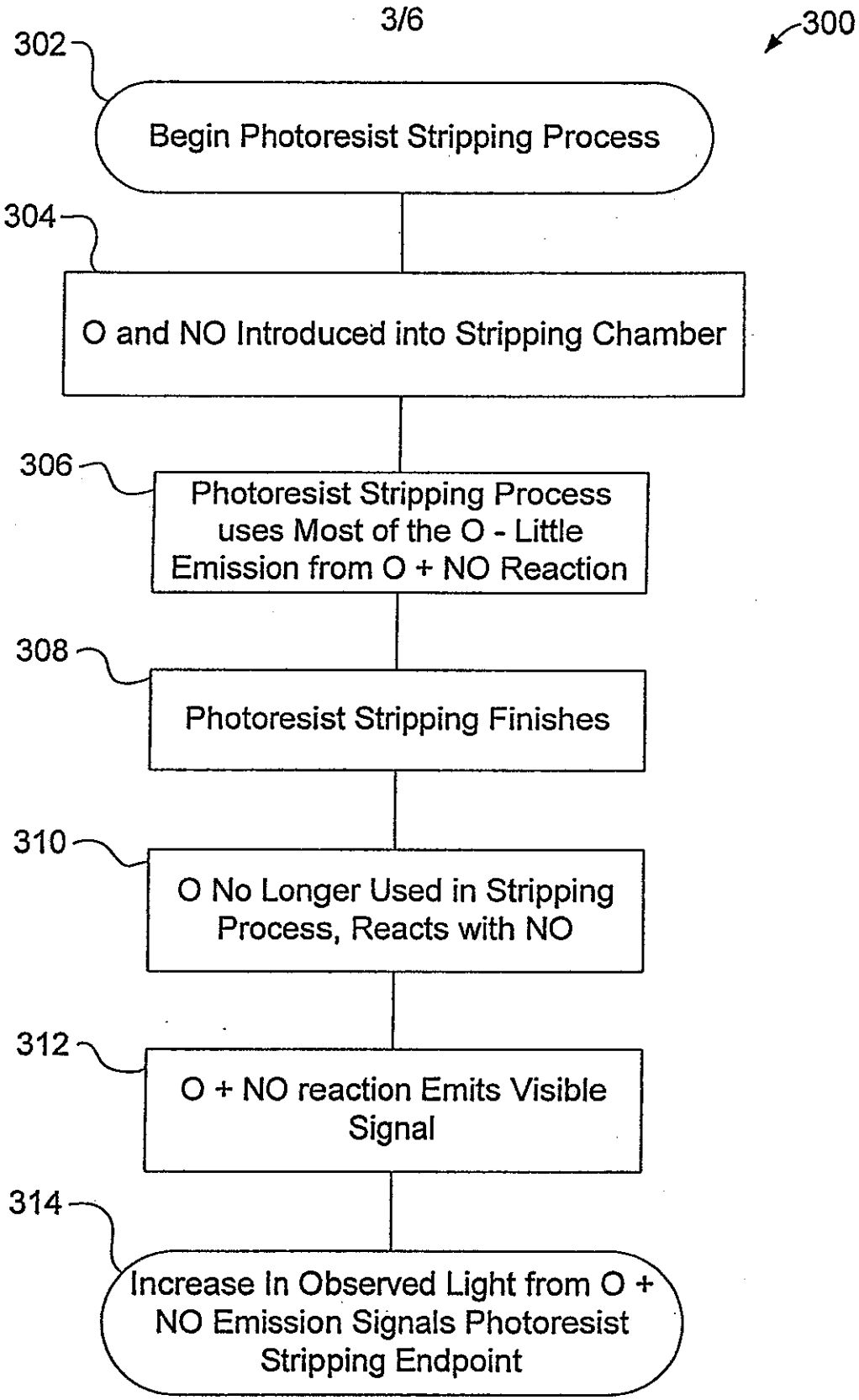

300
302
Begin Photoresist Stripping Process
304
O and NO Introduced into Stripping Chamber
306
Photoresist Stripping Process uses Most of the O - Little Emission from O + NO Reaction
308
Photoresist Stripping Finishes
310
O No Longer Used in Stripping Process, Reacts with NO
312
O + NO reaction Emits Visible Signal
314
Increase In Observed Light from O + NO Emission Signals Photoresist Stripping Endpoint

Fig. 3

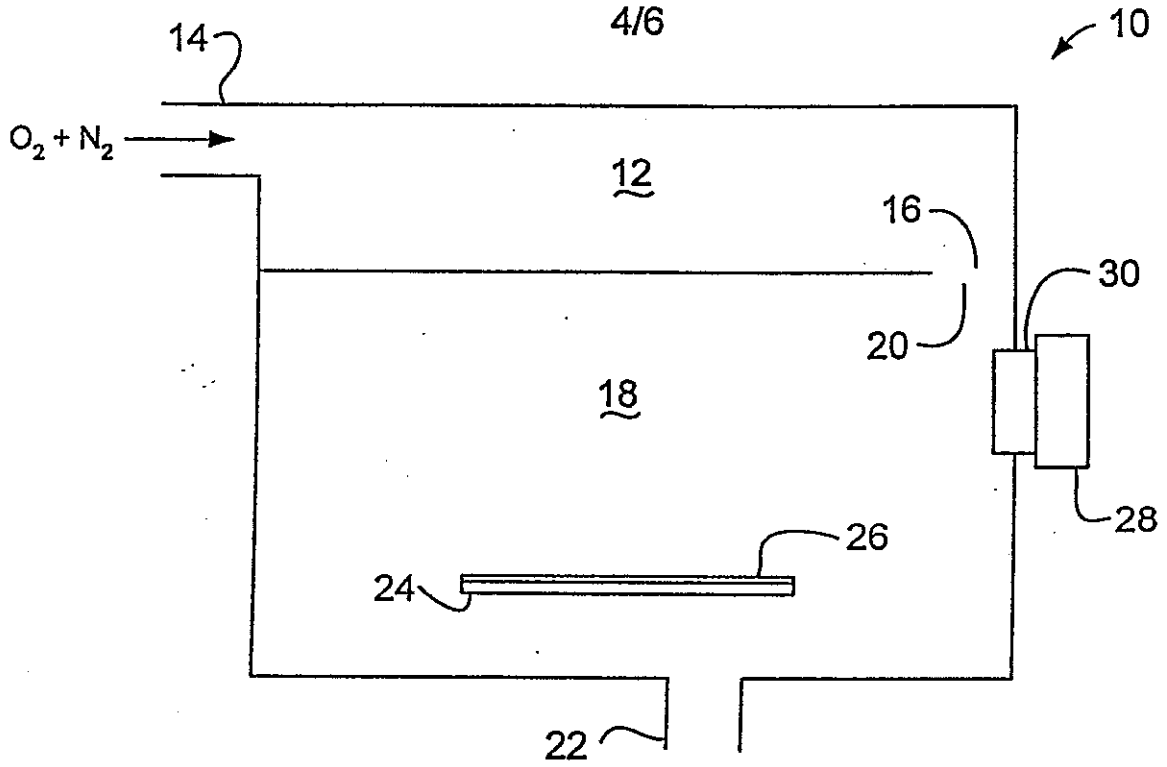

14
10
$O_2 + N_2$
12
16
30
20
18
28
26
24
22

Fig. 4

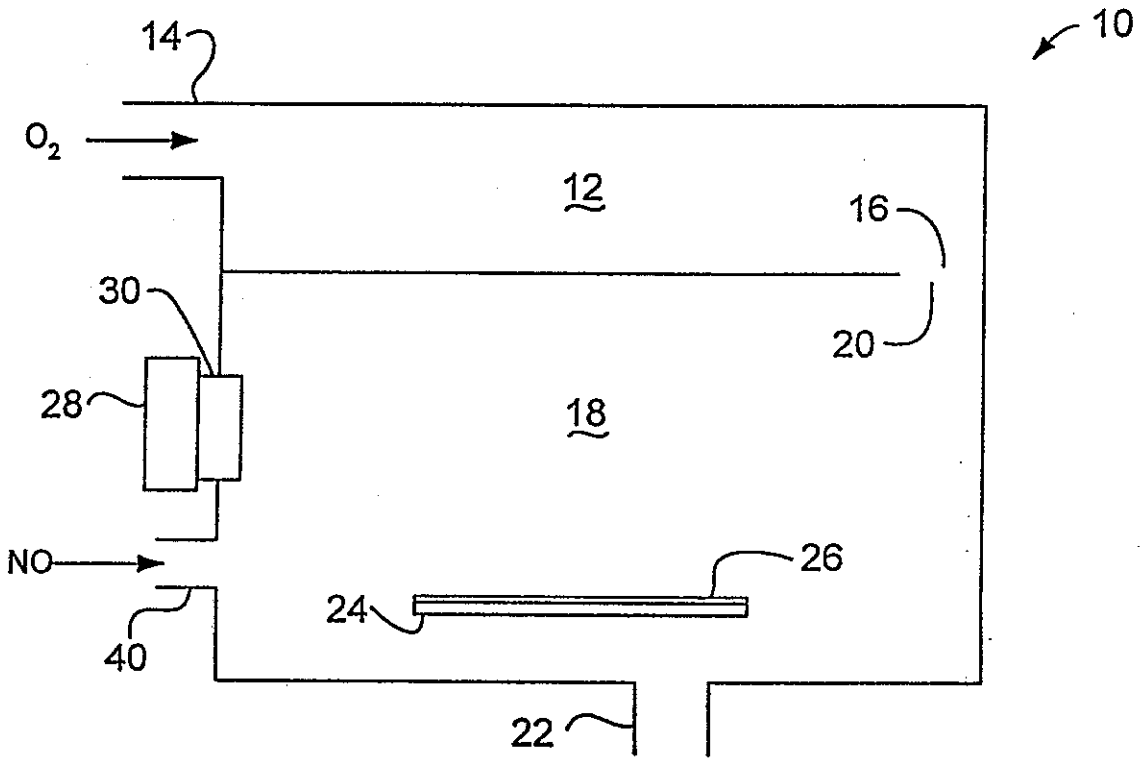

14
10
O_2
12
16
30
20
28
18
NO
26
24
40
22

Fig. 5

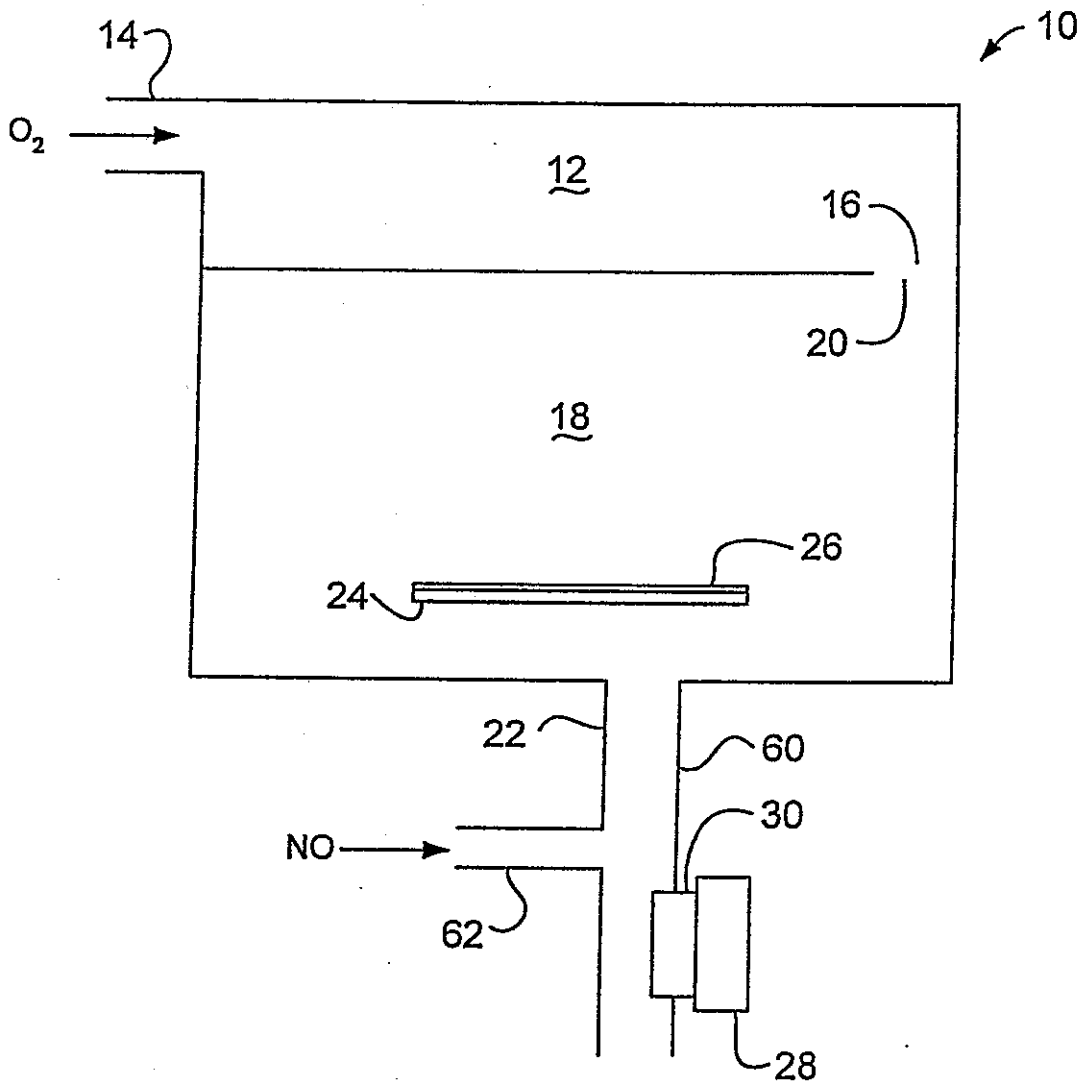


Fig. 6

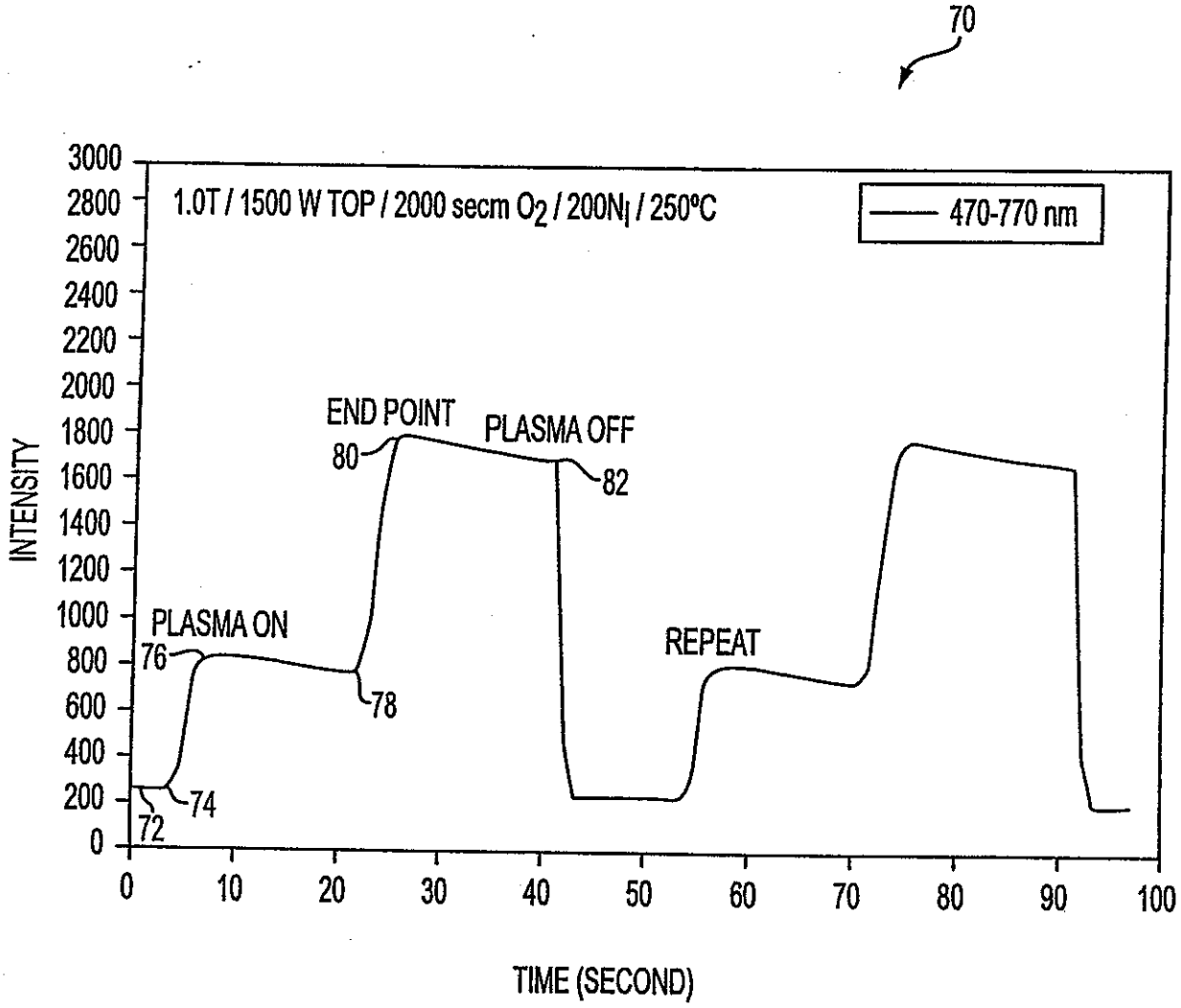

70
1.0T / 1500 W TOP / 2000 secm O_2 / 200N_l / 250°C
470-770 nm
INTENSITY
TIME (SECOND)
END POINT
PLASMA OFF
PLASMA ON
REPEAT
72
74
76
78
80
82
3000
2800
2600
2400
2200
2000
1800
1600
1400
1200
1000
800
600
400
200
0
0
10
20
30
40
50
60
70
80
90
100

FIG. 7